Second Preliminary Amendment USSN 10/571,475 Page 2

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph no. 0003 with the following amended paragraph:

EP 0 747 771 EP 0 747 772 describes an illumination system having a zoom-axicon objective, in whose object plane there is arranged a first diffractive raster element with a two-dimensional raster structure. This raster element is used to increase the geometric light guidance valve (or extendue) of the incident laser radiation slightly and to change the form of the light distribution in such a way that, for example, the result is an approximated circular distribution, annular distribution or quadrupole distribution. In order to change between these illuminating modes, first raster elements are interchanged. A second raster element, which is located in the exit pupil of the objective, is illuminated by the corresponding light distribution and forms a rectangular light distribution, whose form corresponds to the entry surface of a following rod-like light mixing element. means of adjusting the zoom-axicon, the annularity of the illumination and the size of the area that is lit up (illuminated) can be adjusted.

Please replace the paragraph no. 0007 with the following amended paragraph:

Second Preliminary Amendment USSN 10/571,475 Page 3

DE 199 44 760 A1 discloses an illumination device for printing plates which permits modulation of the illumination intensity in the integrated digital screen imaging process (IDSI). In this case, the light from a light source falls onto a digital light modulator having a two-dimensional array of cells, which can be activated and deactivated via a computer-controlled system in order to deflect a specific pattern onto a lightsensitive substrate, which is moved relative to the light In one embodiment, the light modulator comprises a modulator. micro-mirror arrangement (digital mirror device, DMD) having a number of individual mirrors that be driven can individually. During printing, those mirrors which are not used for the exposure of the light-sensitive material are tilted in such a way that they deflect the light beam falling on them away from light-sensitive material. By means of the control system, the number of individual mirrors used in the exposure is thus changed. A similar system is disclosed by—WO 00/36470 WO 01/36470 A2.